

	<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)		Docket Number (Optional) <b>SAET-009 (61966-042)</b>	Application Number <b>10/723,028</b>
	Applicant(s) <b>Robert G. Wiley</b>			
	Filing Date <b>November 26, 2003</b>		Group Art Unit <b>2874</b>	

**U.S. PATENT DOCUMENTS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

**U.S. PATENT APPLICATION PUBLICATIONS**

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

**FOREIGN PATENT DOCUMENTS**

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

**OTHER DOCUMENTS** (Including Author, Title, Date, Pertinent Pages, Etc.)

<b>EK</b>		Michael Fokine and Walter Margulis, "Large increase in photosensitivity through massive hydroxyl formation," OPTICS LETTERS, Vol. 25, No. 5 (March 1, 2000), pp. 302-304.

EXAMINER

*Ellen Kim*

DATE CONSIDERED

*12/7/05*

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.